

ABSTRACT

**DILUTED NITROGEN TRIFLUORIDE THERMAL
CLEANING PROCESS**

The present invention is a method for the dynamic cleaning of semiconductor fabrication equipment and particularly quartzware with thermally activated diluted nitrogen trifluoride at elevated temperatures, typically at the process operation temperature, wherein the cleaning effluent is safely removed and cleaning by-products isolated or diluted to provide for efficient cleaning and rapid restarts of fabrication equipment so cleaned.

Figure 1 of the drawings should accompany the abstract when published